## **EUROPEAN PATENT OFFICE**

## **Patent Abstracts of Japan**

PUBLICATION NUMBER

11297806

PUBLICATION DATE

29-10-99

APPLICATION DATE APPLICATION NUMBER 15-04-98 10103222

APPLICANT: ULVAC CORP:

INVENTOR: NAKAJIMA KOICHI;

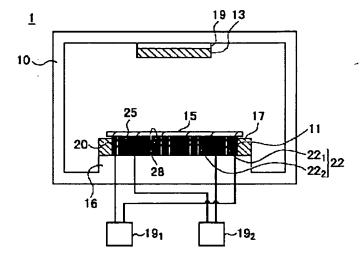
INT.CL.

H01L 21/68 H01L 21/203 H01L 21/205

H01L 21/3065

TITLE

HOTPLATE



ABSTRACT :

PROBLEM TO BE SOLVED: To provide a hotplate of a structure, wherein a substrate is made to heat up at a uniform temperature.

SOLUTION: In a vacuum device 1 having a vacuum tank 10, a heater 22, which is provided in a unit main body 20 of a hotplate 11, is constituted in such a way that the temperature of the outer peripheral part of a suction surface 28 and the temperature of the part on the side more inner than the outer periphery part can be separately set. For example, the heater 22 is split, the outer peripheral parts of the split heaters 22 are respectively constituted of an annular first heater pattern 22<sub>1</sub>, and the interiors of the outer peripheral parts are respectively constituted of a second heater pattern 222. In the case where a substrate 15 is electrostatically adsorbed on the suction surface 28 to heat the substrate 15, the temperature of the peripheral part of the substrate 15 is apt to be reduced lower than that of the part other than the peripheral part, but the substrate 15 is evenly heated up if the heat generation quantity of the first heater patterns 221 are held increased.

COPYRIGHT: (C)1999,JPO